

ABSTRACT

5 An etching solution for titanium-based metals,
tungsten-based metals, titanium/tungsten-based metals, or
their nitrides, which comprises hydrogen peroxide, an
organic acid salt, and water. The etching solution can
be used for uniform etching of titanium-based metals,
tungsten-based metals, titanium/tungsten-based metals, or
their nitrides, with little foaming, and an etching
10 solution can be obtained having an excellent selective
etching property for titanium-based metals, tungsten-
based metals and titanium/tungsten-based metals with
respect to other metals or base materials.